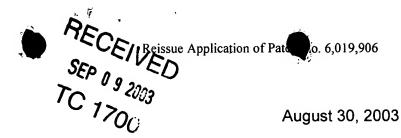
TSMC97-306 Reissue Application no. 10/062,314



1754

#414B 9/16/13

SEP 0 4 2003

CHADEMARTO:

Commissioner of Patents and Trademarks

Washington, D.C. 20231

FROM:

George O. Saile, Reg. No. 19,572 20 Melntosh Drive & Swis Ave

Poughkeepsie, N.Y. 12603

SUBJECT:

Reissue Application of:

Patent #:

6,019,906

Issue Date: Feb. 1, 2000 Inventor: Syun-Ming Ja

Syun-Ming Jang, Ming-Hsin Huang

Title:

Hard Masking Method for Forming Patterned Oxygen

Containing Plasma Etchable Layer

Reissue Serial Number:

10/062,314

Reissue File Date:

Feb. 1, 2002

RESPONSE TO OFFICE ACTION

This is in response to the office action dated July 30, 2003. Please amend the above-identified Reissue application for patent as follows:

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner of Patents and Trademarks, Washington, D.C. 20231 on September 2, 2003

Signature_

Stephen B. Aekerman, Reg. No. 37,761

Date: 9203